

ABSTRACT OF THE DISCLOSURE

A CVD apparatus includes a plurality of first gas pipes connected to a gas mixing port and a plurality of gas vaporizers, respectively, to guide TEB, TEPO and TEOS from an appropriate gas vaporizer to the mixing port.

5 The CVD apparatus also includes a plurality of second pipes connecting a plurality of liquid source origins with the plurality of gas vaporizers, respectively. Respective plurality of first gas pipes and respective plurality of second pipes corresponding to the plurality of first gas pipes constitute pipes of one line. In the comparison of a plurality of pipe lines, the length
10 of the plurality of pipe lines is substantially equal to each other.

Accordingly, a CVD apparatus that can easily deposit a desired CVD film is provided.